Low-optical-loss graphene-based phase modulator operating at mid-infrared wavelength

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Abstract

We numerically analyzed a graphene optical modulator operating at mid-infrared wavelength. We found that the change in an operating wavelength from 1550 nm to 3000 nm enables a phase modulation with a significantly low optical loss by a realistic bias voltage.

1. Introduction

After the first success of exfoliation of single-layer graphene, its exceptional material properties such as zero-bandgap structure with Dirac cones enables various optoelectronic devices. Particularly, a graphene-based optical modulator has gained considerable attention for optical interconnections. Since the first demonstration of a graphene optical modulator on Si photonics platform [1], there has been many reports of graphene optical modulators relying on the change in its absorption coefficient through its chemical potential modulation by a gate voltage. On the other hand, a graphene-based optical phase modulator operating at the telecommunication wavelength has not been experimentally demonstrated yet because the phase shift accompanies a large optical loss within the realistic range of a gate voltage. A large gate voltage may reduce an optical loss, while, in practice, a breakdown in a gate dielectric makes it difficult to apply a large gate voltage [2]. In this work, we have proposed graphene-based optical phase modulators operating at a 3000 nm wavelength. Since the modulation of chemical potential required for π phase shift can be reduced by changing an wavelength from nearinfrared (NIR) to mid-infrared (MIR) wavelength, the optical phase modulation with low optical loss is expected to be achieved within the realistic range of gate voltage.

2. Device structure

A cross-sectional schematic of a graphene optical modulator discussed in this paper is shown in Fig. 1. For a comparison, we analyzed the modulation characteristics operating at 1550 nm and 3000 nm wavelengths. For a single-mode operation at 1550 and 3000 nm, the thicknesses of the Si layer were designed to be 220 and 470 nm, respectively. The widths of the Si waveguides were 440 and 870 nm, respectively. A 7-nm-thick gate dielectric (Al₂O₃) was deposited on Si waveguide and inserted between both graphene layers. The distance between Au electrode and waveguide was assumed not to have no effect on the guided mode. We considered the fundamental TM mode as shown in Fig. 2. When a gate voltage $V_{\rm g}$ is applied between both graphene, the chemical potential of graphene is modulated, which leads changes in refractive index and absorption.



Fig.1 Schematic of graphene optical modulator.



Fig. 2 Electrical field distribution of fundamental TM mode at 1550 nm (broken line in Fig. 1).

3. Result and discussion

In this study, we extracted effective refractive index and absorption of the TM mode by the finite-different eigenmode (FDE) solver in Lumerical software. An atomically thin graphene was modeled as a surface conductivity material model. We assumed the relationship between chemical potential (μ_c) and a gate voltage expressed by

$$\mu_c = \hbar v_F \sqrt{\eta \pi |V_g + V_0|} \quad , \qquad (1)$$

where \hbar is the reduced Plank constant, v_F is the Fermi velocity, V_0 is the voltage offset caused by natural doping (in this simulation we assumed there was no doping on graphene and $V_0 = 0$), and $\eta = 9 \times 10^{16} m^{-2} V^{-1}$, which was estimated using a parallel-plate capacitor model [1]. Figure 3 shows the phase shift and absorption of the TM mode at 1550 nm and 3000 nm as a function of a gate voltage. At both wavelengths, the chemical potential reaches 0.5 eV from the Dirac point when a gate voltage is 2.5 V, resulting in the surface carrier density of $2 \times 10^{13} \text{ cm}^{-2}$ in graphene [3]. It seems very difficult to accumulate more carriers in a metal-oxidesemiconductor structure because of the gate dielectric breakdown [2]. This means that the chemical potential of graphene must be less than 0.5 eV. Thus, the maximum applicable gate voltage was assumed to 2.5 V in this study.

There are two types of carrier transition in graphene, the in



Fig. 3 Phase shift and absorption of the TM mode at wavelength of 1550 and 3000 nm as a function of a gate voltage. We fixed V_{on} at 2.5 V for 1550 nm and 2.0 V for 3000 nm, respectively, and V_{off} is changed to examine the modulation characteristics.



 ΔV (V) Fig. 4 An insertion loss for 1550 nm and 3000 nm wavelength as a function of ΔV .

traband transition and the interband transition. Both mechanisms depend on chemical potential of graphene [4]. When a wavelength was 1550 nm, the absorption caused by the interband transition remains even with a gate voltage of 2.5 V, meaning that a large optical loss is unavoidable for phase modulation. In contrast, at 3000 nm, the absorption caused by the interband transition can be suppressed at a gate voltage of 1.5 V, then the absorption increases gradually because of the intraband transition. Therefore, the phase shift with a low optical loss is achievable with a voltage range from 1.5 V to 2.5 V.

At a 1550 nm wavelength, we assumed that an on voltage $(V_{\rm on})$ was fixed to be 2.5 V to maximize the phase shift. We calculated the modulation characteristics by changing an off voltage $(V_{\rm off})$ from 1.5 V to 2.5 V. At a 3000 nm, $V_{\rm on}$ was fixed to be 2.0 V, and $V_{\rm off}$ was swept from 1.0 V to 2.0 V. In this range, the phase shift is larger than one in the range of 1.5 V to 2.5 V with almost unchanged absorption. For each voltage swing (ΔV) defined by $V_{\rm on} - V_{\rm off}$, we calculated a phase shifter length for π phase shift, then calculated an insertion loss as



Fig. 5 Change in optical loss for p phase shift at 1550 nm and 3000 nm wavelengths as function of ΔV .

shown in Fig. 4. In the case of 1550 nm, the insertion is greater than 20 dB, making a realistic phase modulator difficult. On the other hand, in the case of 3000 nm, the insertion loss decreases as ΔV gets increased. When ΔV is 1 V, the insertion loss is approximately 5 dB, which is more realistic loss as compared with that at 1550 nm. We also calculate a change in optical loss when a phase is modulated from 0 to π (Δ Loss), which affects an extinction ratio for modulation. Figure 5 shows Δ Loss as a function of ΔV . As compared with 1550 nm, we can achieve quite small Δ Loss at 3000 nm. Thus, graphene is more suitable for optical phase modulation at a MIR wavelength.

4. Conclusion

We have numerically analyzed graphene optical modulators operating at wavelengths of 1550 and 3000 nm. At 1550 nm, an insertion loss and attenuation change for π shift are too large for realistic phase modulation. In contrast, we have revealed that a graphene phase modulator gives much less insertion loss and attenuation change at the wavelength of 3000 nm. Thus, we have shown the feasibility of optical phase modulation based on graphene operating at MIR wavelength.

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References

- [1] Ming Liu *et al.*, "A graphene-based broadband optical modulator", *Nature*, **474**, 64-67(2011).
- [2] T. Kayoda, J. Han, M. Takenaka and S. Takagi, "Evaluation of Chemical potential for graphene optical modulators based on the semiconductor-metal transition," *International Conference on Group IV Photonics*, ThD5 (2013).
- [3] G. W. Hanson, "Dyadic Green's functions and guided surface waves for a surface conductivity model of graphene" *Journal of Appl. Phys.*, 103, no. 6, 064302 (2008).
- [4] S. A. Mikhailov and K. Ziegler, "New Electromagnetic Mode in Graphene", *Phys. Rev. Lett.*, **99**, 016803 (2007).